

AMEC PD5 SYSTEM CONFIGURATION

System Configuration:

- Process Application : GaN Epitaxy
- Vintage : Oct 2020
- Wafer Type : 11x4", 6x6", 3x8" GaN on Silicon/SiC
- Transfer Module : Yes, able to support up to 4 chambers
- Pump : Edwards iXH645H
- Chiller : SMC
- MFCs Type : Horiba
- MO Configuration : TMGa1/2, TMAI1/2, TEGa, Cp2Fe, TMIIn, Cp2Mg
- Doping Source : 2x External Dopant inlet
- Inline Purifiers : H2, N2, NH3
- Dew Point Sensor : H2, N2

Process Startup:

- Process demonstration for Breakdown Voltage >650V
- 650V HEMT recipe will be provided